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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION OF

Confirmation No.: 7680

VAN DER LAAN *et al.*

Group Art Unit: 2851

Appln. No.: 09/943,088

Examiner: H. NGUYEN

Filed: August 31, 2001

Title: METHOD OF OPERATING A LITHOGRAPHIC APPARATUS, LITHOGRAPHIC APPARATUS, METHOD OF MANUFACTURING A DEVICE MANUFACTURED THEREBY

January 2, 2003

\* \* \* \* \*

**AMENDMENT**

Hon. Commissioner of Patents  
Washington, D.C. 20231

Sir:

In response to the Office Action dated September 13, 2002, please amend the above-identified application as follows:

**IN THE SPECIFICATION:**

Page 9, delete the whole paragraph starting in line 5 and replace it with the following new paragraph:

b) [0069] a projection system ("lens") PL (e.g. a quartz and/or CaF<sub>2</sub> lens system or catadioptric system comprising lens elements made from such materials, or a mirror system) for imaging an irradiated portion of the mask MA onto a target portion C (e.g. comprising one or more dies) of substrate W. As shown in Figure 1, mask MA is provided with alignment marks M<sub>1</sub> and M<sub>2</sub> and substrate W is provided with alignment marks P<sub>1</sub> and P<sub>2</sub> such that the substrate W and the mask can be aligned relative to each other.

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